

**PROCESS FOR FABRICATING A TRANSISTOR WITH A METAL GATE,
AND CORRESPONDING TRANSISTOR**

ABSTRACT

5

A phase of siliciding a transistor includes formation, from a first metal (8), of a first metal silicide (80) on the drain and source regions, while the gate region (30) is protected by a layer of hard mask (40), removal of the hard mask, formation, from a second metal (9), of a second metal silicide (90) on
10 the gate region, while the first metal silicide (80) is protected by the second metal (9), and removal of the second metal (9).